

Novel Photochemical Reactions of Dibenzodisilacyclohexadiene with Ketones^{†,1)}

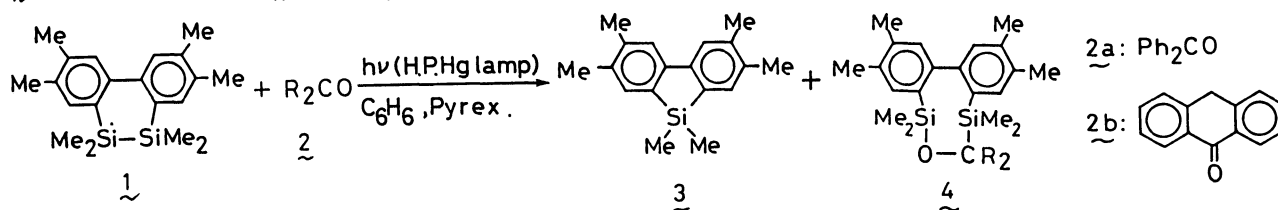
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Dibenzodisilacyclohexadiene reacts with ketones and formaldehyde, under photolytic conditions, to give a variety of products depending on the nature of the ketones used. A compound having 2-sila-3-oxabicyclo[3.2.2]nona-6,8-diene structure was isolated as a result of intramolecular trapping of a cyclohexadienyl radical.

In previous papers,²⁾ we have reported several new photochemical reactions of dibenzodisilacyclohexadiene and derivatives. Herein an entirely new photochemical addition reaction of dibenzodisilacyclohexadiene with ketones will be reported.

Irradiation of a benzene solution of 1³⁾ in the presence of small excess benzophenone (2a) gave, in addition to the silylene extrusion product 3 (46%), a new compound 4a was obtained in 40% yield. A similar reaction of 1 with anthrone (2b) gave adducts 4b and 3 in 52 and 22% yields, respectively.⁴⁾

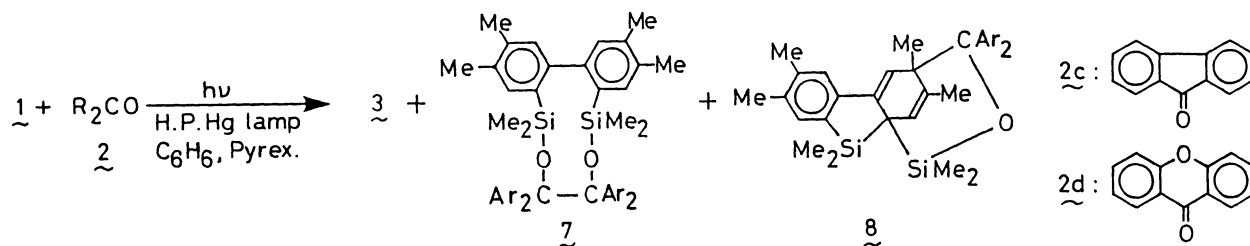


The possibility of an S_H2 reaction,⁵⁾ that the Si-Si bond reacted with photochemically excited benzophenone, was ruled out by the fact that no reaction occurred at all by using a light of wavelength longer than 340 nm, by which benzophenone alone was excited. Therefore, photoaddition can be explained by the stepwise reactions initiated by homolysis of the Si-Si bond to give a biradical (5).^{2a)} A silyl radical terminal of 5 adds to a ketone to give a key biradical (6), which affords eventually the adduct by intramolecular recombination.

On the other hand, the reaction of 1 with fluorenone (2c) gave a 1:2 adduct (7c, 14%) and 3 (16%), but the major product was an entirely new 1:1 adduct (8c) formed in 57% yield.⁶⁾ No 1:1 adduct corresponding to 4 was obtained. A similar reaction occurred with 9-xanthenone (2d) to give 7d (15%), 8d (41%), and 3 (15%).⁷⁾

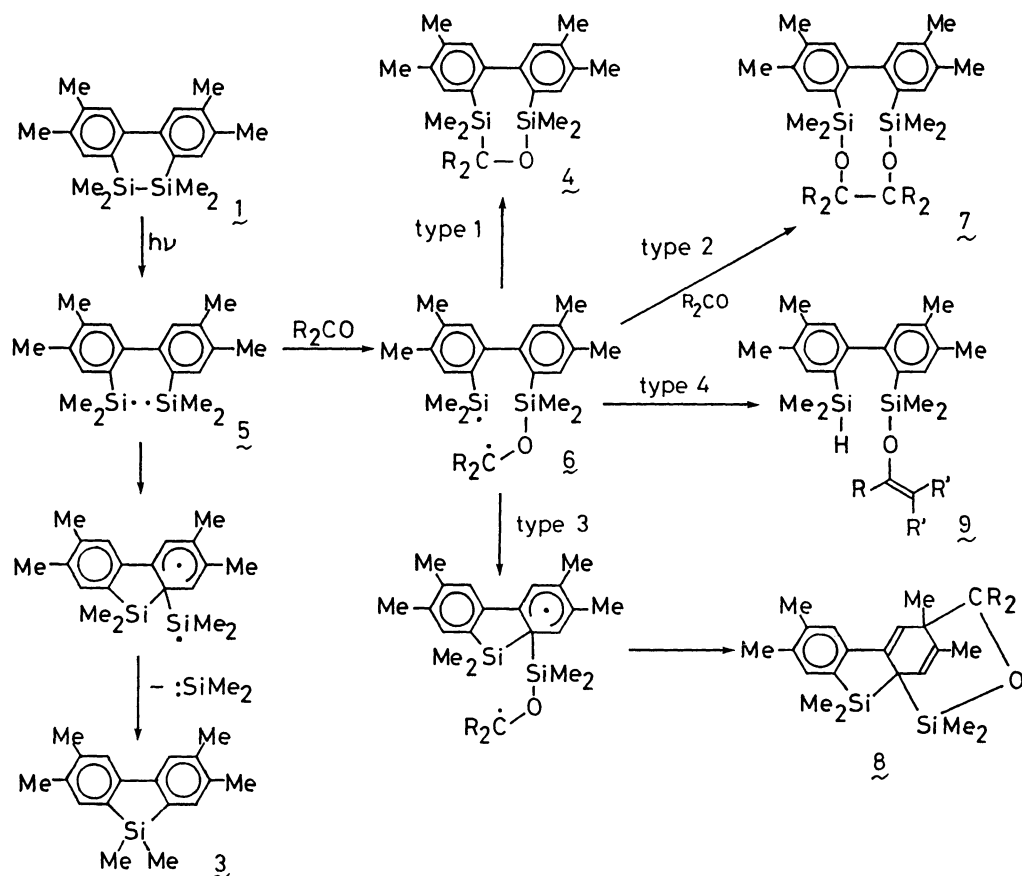
It is interesting to note that the benzene structure of 1 was destroyed in the photoproducts 8. This is a rare example of intramolecular trapping of a cyclohexadienyl radical. The structures of these compounds were identified on the basis of the spectroscopic data.⁸⁾ The molecular structure of 8d was further confirmed by X-ray crystallographic analysis.^{8b)}

[†] Dedicated to the late Professor Ryozo Goto, the first Editor of this journal.



The formation of $\underline{8}$ provides evidence for the existence of an efficient ipso-silylation process involving $\underline{6}$. It has been previously suggested that the silylene elimination process includes also an intramolecular ipso-silylation process.⁹⁾

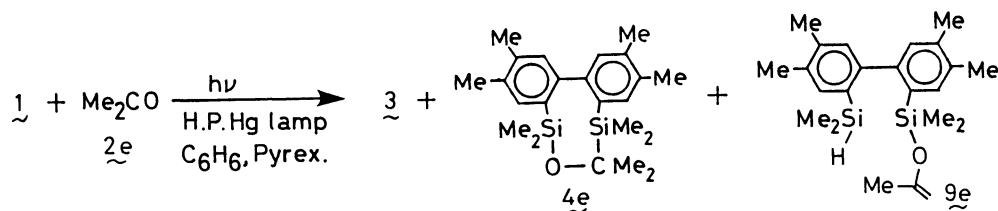
The formation of the products $\underline{7}$ and $\underline{8}$ can be explained by the stepwise mechanism involving the biradical $\underline{6}$ as a key intermediate as shown in Scheme 1. While biradicals $\underline{6}$ gave the adduct $\underline{4}$ in the reaction with benzophenone ($\underline{2a}$) and anthrone ($\underline{2b}$), it afforded a different type of adducts with fluorenone ($\underline{2c}$) and 9-xanthone ($\underline{2d}$). The difference in the behavior of the intermediate radical $\underline{6}$ may be explained by longer life-time for $\underline{2c}$ - and $\underline{2d}$ -derived radicals.



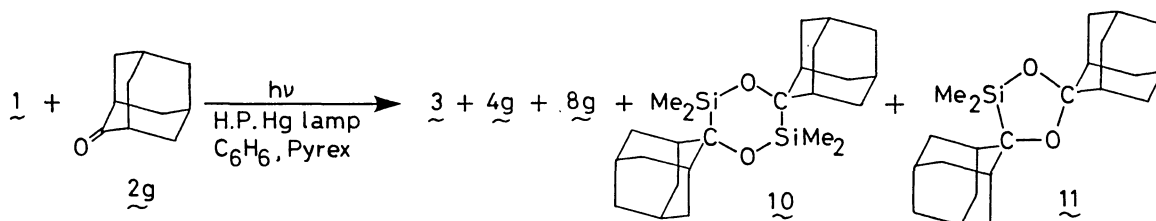
Scheme 1.

Photolysis of $\underline{1}$ in the presence of acetone ($\underline{2e}$) gave the fourth type of adduct, $\underline{9e}$ (43%), in addition to a 1:1 adduct ($\underline{4e}$, 27%) and $\underline{3}$ (5%).¹⁰⁾ The structure of $\underline{9e}$ was determined by various spectroscopic data. A strong sharp absorption band at 2220 cm^{-1} due to Si-H stretching in an IR spectrum supports strongly the assigned structure.

The formation of $\underline{9e}$ is explained by the intramolecular disproportionation of biradical $\underline{6e}$. Although hydrogen abstraction from hydrocarbon by a silyl radical is not favorable thermodynamically, intermolecular disproportionation of silyl radicals to afford hydrosilane and silaethene has been reported by several groups.¹¹⁾ We also reported another example of intermolecular disproportionation.¹²⁾ The reaction of $\underline{1}$ with diisopropyl ketone ($\underline{2f}$, R = Me₂CH-) gave the similar disproportionation product $\underline{9f}$ (R = i-Pr, R' = Me) in 24% yield.¹³⁾ The direct recombination product similar to $\underline{4e}$ was not detected in this case. Probably, large steric hindrance of two isopropyl groups may hinder recombination.



Photolysis of $\underline{1}$ in the presence of adamantanone ($\underline{2g}$) gave $\underline{3}$, $\underline{4g}$, $\underline{8g}$, $\underline{10}$, and $\underline{11}$ in 30, 23, 5, 21, and 10% yields, respectively.¹⁴⁾ The formation of $\underline{8g}$ is a result from the reduced rate of recombination of the biradical ($\underline{6g}$) by large steric hindrance exerted by the adamantyl group. The compounds $\underline{10}$ and $\underline{11}$ were produced by the reaction of adamantanone with the dimethylsilylene formed from $\underline{1}$ as reported by Ando et al.¹⁵⁾



Finally, the reaction of $\underline{1}$ with formaldehyde ($\underline{2h}$), freshly prepared by a pyrolysis of paraformaldehyde in toluene, was examined. The isolated products were $\underline{3}$ and $\underline{4h}$ (R = H) in 37 and 27% yields, respectively.

The photoreaction of $\underline{1}$ with ketones and formaldehyde are summarized in Scheme 1. Whereas photolysis of $\underline{1}$ gave $\underline{3}$ via an intramolecular ipso-silylation of $\underline{5}$ in the absence of ketone, the silyl radical terminal of $\underline{5}$ affords $\underline{6}$ when a carbonyl compound exists. Thus two reactions compete each other. The biradical $\underline{6}$ undergoes four types of reactions: recombination (type 1), further addition to the second ketone (type 2), intramolecular ipso-silylation followed by recombination (type 3), and intramolecular disproportionation (type 4).

References

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- 2) a) M. Kira, K. Sakamoto, and H. Sakurai, J. Am. Chem. Soc., **105**, 7469 (1983);
b) H. Sakurai, K. Sakamoto, and M. Kira, Chem. Lett., **1984**, 1213; c) H. Sakurai, K. Sakamoto, and M. Kira, *ibid.*, **1984**, 1379.
- 3) The tetramethyl derivative ($\underline{1}$), instead of unsubstituted one, is used in this paper because of easiness of preparation from o-xylene: mp 184 °C.
- 4) $\underline{4a}$: white crystals; mp 185 °C; ¹H NMR (CCl₄, δ) -0.66 (s, 3H), -0.65 (s, 3H),

- 0.42 (s, 3H), 0.61 (s, 3H), 2.24 (bs, 12H), 6.9-7.4 (m, 14H); ^{29}Si NMR (CDCl_3 , δ) -0.8, -2.6. $\underline{4b}$: white crystals; mp 218-220 °C; ^1H NMR (CCl_4 , δ) -0.95 (s, 3H), -0.24 (s, 3H), 0.17 (s, 3H), 0.63 (s, 3H), 2.33 (s, 3H), 2.43 (s, 6H), 2.53 (s, 3H), 4.07 (bs, 2H), 6.68 (bs, 1H), 7.0-7.6 (s, 10H), 7.66 (bs, 1H).
- 5) A. Hosomi and H. Sakurai, *J. Am. Chem. Soc.*, 94, 1385 (1972).
- 6) $\underline{7c}$: white crystals; mp > 280 °C; ^1H NMR (CCl_4 , δ) -0.39 (s, 6H), 0.03 (s, 6H), 2.43 (bs, 12H), 5.68 (d, 2H, $J = 7$ Hz), 6.53 (t, 2H, $J = 7$ Hz), 6.7-7.5 (m, 16H); ^{29}Si NMR (CDCl_3 , δ) 3.8. $\underline{8c}$: white crystals; mp 179 °C (dec.); ^1H NMR (CCl_4 , δ) -0.18 (s, 3H), 0.22 (s, 3H), 0.31 (s, 3H), 0.47 (s, 3H), 0.60 (s, 3H), 1.74 (d, 3H, $J = 1.3$ Hz), 2.31 (s, 3H), 2.38 (s, 3H), 6.09 (s, 1H), 6.39 (q, 1H, $J = 1.3$ Hz), 7.15-7.65 (m, 10H); ^{29}Si NMR (CDCl_3 , δ) 7.0, -16.0.
- 7) $\underline{7d}$: white crystals; mp > 280 °C; ^1H NMR (CCl_4 , δ) -0.27 (s, 6H), 0.20 (s, 6H), 2.46 (s, 6H), 2.48 (s, 6H), 5.8-7.7 (m, 20H). $\underline{8d}$: white crystals; mp 205 °C (dec.); ^1H NMR (CCl_4 , δ) 0.07 (s, 3H), 0.32 (s, 3H), 0.58 (s, 3H), 0.61 (s, 3H), 0.94 (s, 3H), 1.41 (d, 3H, $J = 1.3$ Hz), 2.24 (s, 3H), 2.48 (s, 3H), 5.67 (s, 1H), 6.32 (q, 1H, $J = 1.3$ Hz), 7.00-7.80 (m, 10H).
- 8) a) Satisfactory high-resolution MS and/or elemental analyses were obtained for all the new compounds. b) The X-ray structure of $\underline{8d}$ will be reported later.
- 9) H. Sakurai, Y. Nakadaira, M. Kira, H. Sugiyama, K. Yoshida, and T. Takiguchi, *J. Organomet. Chem.*, 184, C36 (1980).
- 10) $\underline{4e}$: colorless oil; ^1H NMR (CCl_4 , δ) 0.1-0.2 (12H, m), 1.8 (3H, s), 2.20 (6H, s), 2.25 (6H, s), 4.00 (1H, bs), 4.05 (1H, bs), 4.15 (1H, septet, $J = 6.8$ Hz), 7.01 (1H, bs), 7.04 (1H, bs), 7.34 (1H, bs), 7.47 (1H, bs). $\underline{9e}$: colorless oil; ^1H NMR (CCl_4 , δ) -0.66 (3H, s), -0.63 (3H, s), 0.24 (3H, s), 0.34 (3H, s), 1.17 (3H, s), 1.20 (3H, s), 2.30 (12H, s), 6.96 (2H, bs), 7.18 (1H, bs), 7.29 (1H, bs).
- 11) S. K. Tokach and R. D. Koob, *J. Am. Chem. Soc.*, 102, 376 (1980); B. J. Cornett, K. Y. Choo, and P. P. Gaspar, *ibid.*, 102, 377 (1980).
- 12) H. Sakurai, Y. Nakadaira, and H. Sakaba, *Organometallics*, 2, 1484 (1983).
- 13) $\underline{9f}$: colorless oil; ^1H NMR (CCl_4 , δ) -0.04 (s, 3H), 0.06 (s, 3H), 0.09 (d, 3H, $J = 3.5$ Hz), 0.15 (d, 3H, $J = 3.5$ Hz), 1.00 (d, 3H, $J = 6.8$ Hz), 1.02 (d, 3H, $J = 6.8$ Hz), 1.48 (s, 3H), 1.68 (s, 3H), 2.32 (s, 3H), 2.35 (s, 3H), 2.38 (s, 3H), 2.41 (s, 3H), 2.83 (septet, 1H, $J = 6.8$ Hz), 4.10 (septet, 1H, $J = 3.5$ Hz), 6.92 (bs, 1H), 7.02 (bs, 1H), 7.23 (bs, 1H), 7.51 (bs, 1H).
- 14) $\underline{4g}$: white crystals; mp 184-185 °C; ^1H NMR (CCl_4 , δ) -0.67 (3H, s), -0.60 (3H, s), 0.47 (3H, s), 0.52 (3H, s), 1.2-2.2 (m, 14H), 2.3-2.4 (12H, m), 6.96 (1H, bs), 6.99 (1H, bs), 7.20 (1H, bs), 7.23 (1H, bs). $\underline{8g}$: colorless oil; ^1H NMR (CCl_4 , δ) 0.20 (s, 3H), 0.23 (s, 3H), 0.38 (s, 3H), 0.43 (s, 3H), 0.90 (s, 3H), 1.2-2.1 (m, 14H), 1.90 (d, 3H, $J = 1.5$ Hz), 2.30 (s, 3H), 3.03 (s, 3H), 5.67 (s, 1H), 6.16 (q, 1H, $J = 1.5$ Hz), 6.70 (bs, 1H), 7.15 (bs, 1H). $\underline{4h}$: colorless oil; ^1H NMR (CCl_4 , δ) -0.51 (3H, s), -0.50 (3H, s), 0.37 (3H, s), 0.41 (3H, s), 2.37 (6H, s), 2.41 (6H, s), 3.32 (1H, d, $J = 14.4$ Hz), 3.46 (1H, d, $J = 14.4$ Hz), 6.99 (2H, bs), 7.23 (1H, bs), 7.31 (1H, bs).
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